

IC-PLANTS 2009 Time Table

Jan. 22

9	00	Registration	
	50	Welcome	
10	00	I-1	Shigeaki ZAIMA (Nagoya University, Japan) <i>Challenges in Si Nanoelectronics: Materials and Processes</i>
	40	I-2	Michael Kong (Loughborough University, UK) <i>Cold Atmospheric Plasmas as an Infection Control Strategy</i>
11	20	O-1	H. Matsuura , T. Kiriishi, K. Nakano (Osaka Prefecture University) <i>Effect of Rare Gas Flow and Electrode Polarity on the DC Atmospheric Discharge</i>
	40	O-2	T. Morita , O. Sakai, T. Shirafuji, K. Tachibana (Kyoto University) <i>Decomposition of organic substances in liquid using gas-liquid-interface plasmas, and its analysis with FTIR spectroscopy</i>
12	00	Lunch	
13	20	I-3	Noritsugu Umehara (Nagoya University, Japan) <i>Ultra low friction of Carbon Nitride coatings</i>
	40	I-4	Pascal Chabert (CNRS-Ecole Polytechnique, France) <i>Physics of dual-frequency capacitive discharges</i>
14	00	I-4	K. Ando , T. Kimura, T. Yamaguchi, K. Takeda, K. Kubota, C. Koshimizu, A. Kono, M. Sekine, M. Hori (Nagoya U., TEL AT Ltd) <i>Measurements of electron energy distribution function in dual frequency capacitively coupled plasma using laser Thomson scattering</i>
	40	O-3	
15	00	Break	
	20	I-5	William Graham (Queens University Belfast, UK) <i>Electronegative plasmas: The pluses and minuses</i>
16	00	O-4	R. Boswell (Australian National University) <i>Control of EEPF and plasma potential by varying the plasma system length</i>
	20	O-5	B. B. Sahu (Indian Institute of Technology) <i>Evidence of Landau damping in low pressure helicon discharges</i>
16:40 ~ 18:15 Poster			

18:30 ~ 20:00 Banquet

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9	00	Registration	
	40	I-6	Toshio Hayashi (Nagoya University, Japan) <i>Quantum chemical approach to reaction in process plasma</i>
10	20	I-7	Peter Awakowicz (Ruhr-University Bochum, Germany) <i>HID lamps: A high pressure micro discharge</i>
	40	O-6	W. Soliman , T. Nakano, N. Takada, K. Sasaki (Nagoya U.) <i>Synthesis dynamics of nanoparticles produced by laser ablation of a solid target immersed in</i>
11	20	O-7	Y. Yang , Y. Li, M. Tanemura, M. Nogami (E. China U. of Sci & Tech, Nagoya Tech) <i>Surface enhanced Raman scattering of Au nanoneedles</i>
	40	O-8	D. H. Lee, S. W. Kim, W. J. Lee (KAIST, Korea) <i>Control over Wall Number of Carbon Nanotube Array</i>
12	00	Lunch	
13	20	I-8	Jeon G. Han (SungKyunKwan University, Korea) <i>Plasma control for high conductivity TCO film</i>
	40	I-9	Yuichi Setsuhara (Osaka University, Japan) <i>Combinatorial Plasma-Process Analyzer for Development of Plasma Nano-Fabrication Pr</i>
14	00	I-9	
	40	O-9	W. M. Nakamura , Y. Kawashima, M. Tanaka, H. Sato, H. Matsuzaki, K. Koga, M. Shiratani (Kyus) <i>High Deposition Rate of Highly Stable a-Si:H Films by Magnetically Enhanced Multi-hollow Discharges</i>
15	00	Break	
	20	I-10	Kostya Ken Ostrikov (Plasma Nanoscience Centre Australia, Australia) <i>Plasma nanoarchitectronics: a novel platform for future nanotechnologies</i>
16	00	O-10	W. Sakaguchi , S. Kajita, N. Ohno, M. Takagi (Nagoya U.) <i>Formation condition of fiberform nanostructured tungsten by helium plasma irradiation</i>
	20	O-11	X. Zhong , X. Wu and K. Ostrikov (Shanghai Jiao Tong U., China, CSIRO, Australia) <i>Enhancement of Precision and Throughput of Nanopore Processing in Dielectric Template-Assisted Nanoarray Synthesis by Using Pulsed Bias</i>
	40	Closing	